

10-20-05

IFW

Docket Number: 24061.69 (TSMC2002-1055/1057)
Customer No. 42717



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:
Yu Min Lin, et al.

Serial No.: 10/763,643

Filed: January 23, 2004

For: System and Method for Integration of
HfO₂ and RTCVD Ply-Silicon

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Docket No.: 24061.69
(TSMC2002-1055/1057)

Group Art Unit: 2891

Examiner: Asok K. Sarkar

Conf. No.: 7730

Commissioner for Patents
Mail Stop: Amendment
P.O. Box 1450
Alexandria, VA 22313-1450

RESPONSE TO NON-FINAL OFFICE ACTION OF JULY 19, 2005

This paper is submitted in response to the Non-Final Office Action mailed July 19, 2005.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 13 of this paper.